## INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)

Docket Number (Optional) BU9-98-110	Application Number 09/298,786			
Applicant(s) Armbrust et al	• <b>=</b>			
Filing Date 04/23/99	Group Art Unit			

## U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	IF APPR	NO ES
pnk		5,447,887	09/05/95	Filipiak et al.			Ť.	
DAIL		5,633,047	05/1997	Brady et al.	427	437		•
pHK		4,505,029	03/1985	Owyang et al.	427	89		
pnll		5,833,758	04/1997	Linn et al.	134	1.2		
BHK		5,503,704	04/1996	Bower et al.	427	399		
onk		6,046,101	04/2000	Dass et al.	438	791		
bHK		5,844,317	12/1998	Bertolet et al.	257	773		
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				FOREIGN PATENT DOCUMEN	TS			
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
		200011211111111111111111111111111111111	2/112	CONTRI	CLINOS	SUBCLASS	YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

IBM Technical Disclosure, Cronin et al., "Copper/Polyimide Structure with Selective Cu3Si/Si02 Etch Stop," Vol. 37, No. 06A June 1994, p.53.

MUL

EXAMINER

Donghee Kang

DATE CONSIDERED

12-21-00

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.